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Application Number	10/063,049
Filing Date	March 14, 2002
First Named Inventor	Ryza et al.
Group Art Unit	~~1723~~ 1756
Examiner Name	~~Unknown~~ DUDA
Attorney Docket Number	TEX1100

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U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number Number	Class/Subclass	Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
KAD	A1	5013366	134/1	--	05/07/91	Jackson et al.
KAD	A2	6277753	438/692	B1	08/21/01	Mullee et al.
KAD	A3	6331487	438/692	B2	12/18/01	Koch
KAD	A4	20010008800	———	A1	07/19/01	Koch
KAD	A5	6306564	430/329	B1	10/23/01	Mullee
KAD	A6	6224774	210/634	B1	05/01/01	DeSimone et al.
KAD	A7	5377705	134/95.3	--	01/03/95	Smith, et al.
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Examiner Signature	KDuda	Date Considered	12-8-03

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Examiner Initials	Cite No.	Country Code	Number	Kind Code (if known)	Publication Date MM-DD-YYYY (Number 43)	Name of Patentee or Applicant of Cited Document
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KMD	B2	PCT	WO 02/15251	A1	08/14/00	Tokyo Electron Limited
KMD	B3	EP	0 397 826	B1	12/16/92	Hughes Aircraft Company
	B4	JP	60 192333	A	9/30/85	Hitachi Seisakusho

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Date
KMD	C1	KING, et al., "The Mutual Solubilities of Water with Supercritical and Liquid Carbon Dioxide", The Journal of Supercritical Fluids, Volume 5, pages 296-302.	May 1992
KMD	C2	PERRY, et al., "Chemical Engineers' Handbook", 5th Edition, pp. 21-11 to 21-14 (4 sheets).	1973
KMD	C3	Phase Diagram for CO_2 as found at http//www.chem.uncc.edu/faculty/murphy/1252/Chapter11B/sldoo4.htm	February 7, 2002
KMD	C4	Bruan, et al., "Photostrip faces 300 mm, copper and low-k convergence," 7 pages, Semiconductor International.	September 2000
KMD	C5	Sundararajan, et al., "Block copolymers as supercritical CO_2 developable photoresists" Department of Materials Science and Engineering, pp. 130-131.	--
KMD	C6	Rubin, et al., "A Comparison of Chilled DI Water/Ozone and CO_2-Based Supercritical Fluids as Replacements for Photoresist-Stripping Solvents," International Electronics Manufacturing Technology Symposium, pp. 308-314.	January 1998
KMD	C7	Gabor, et al., "Block and Random Copolymer Resist Designed for 193 nm Lithography and Environmentally Friendly Supercritical CO_2 Development," SPIE Vol. 2724, pp. 410-417.	June 1996
KMD	C8	Wetmore, et al., "Supercritical Fluid Processing: A New Dry Technique for Photoresist Developing," SPIE Vol. 2438, pp. 694-703.	June 1995

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